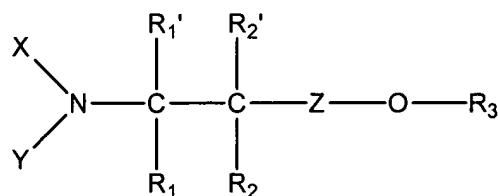


IN THE CLAIMS:

1. (Previously Presented) A resist and etching residue remover composition comprising:
from about 1 wt% to about 30 wt% of N,N-diethylhydroxylamine
from about 20 wt% to about 80 wt% of a two-carbon atom linkage alkanolamine
compound having the formula



wherein R_1 , R_1' , R_2 , R_2' , and R_3 are, independently in each case, hydrogen or a linear, branched, or cyclic hydrocarbon containing from 1 to 7 carbon atoms, wherein Z is a group having the formula $(-Q-CR_1R_1'-CR_2R_2')_m$, such that m is a whole number from 0 to 3, R_1 , R_1' , R_2 , and R_2' are independently defined in each repeat unit, if $m > 1$, within the parameters set forth for these moieties above, and Q is independently defined in each repeat unit, if $m > 1$, each Q being independently either -O- or -NR₃-, and wherein X and Y are, independently in each case, hydrogen, a C₁-C₇ linear, branched, or cyclic hydrocarbon, or a group having the formula -CR₁R₁'-CR₂R₂'-Z-F, with F being either -O-R₃ or -NR₃R₄, where R₄ is defined similarly to R_1 , R_1' , R_2 , R_2' , and R_3 above, and with Z, R_1 , R_1' , R_2 , R_2' , and R_3 defined as above, or wherein X and Y are linked together form a nitrogen-containing heterocyclic C₄-C₇ ring, wherein the two-carbon atom linkage alkanolamine compound comprises 2-(2-aminoethylamino)-ethanol; and

from about 0.1 wt% to about 15 wt% of a corrosion inhibitor which comprises gallic acid, catechol, or an ethylenediamine tetracarboxylic acid compound;

wherein the composition is substantially free of hydroxylamine and of fluoride ions, and the composition is capable of removing residue from a metal or metal alloy substrate or a metal or metal alloy substrate layer, while maintaining an acceptably low etch rate with respect to the metal or metal alloy substrate or substrate layer.

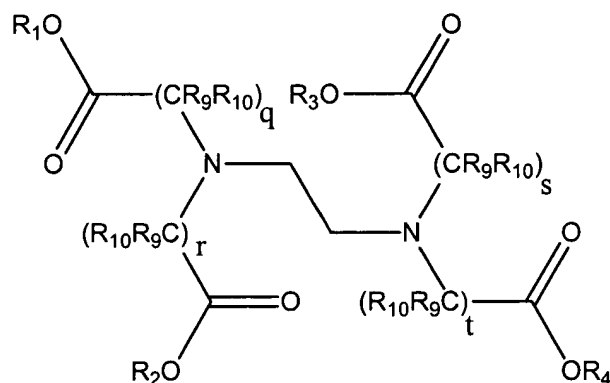
2. (Previously Presented) The composition of claim 1, further comprising water in an amount from about 5 wt% to about 40 wt%.

3. (Previously Presented) The composition of claim 1, wherein the composition is substantially free from water.

4. (Previously Presented) The composition of claim 1, further comprising a polar organic solvent in an amount from about 5 wt% to about 15 wt%.

5. (cancelled)

6. (Previously Presented) The composition of claim 1, wherein the corrosion inhibitor comprises an ethylenediamine tetracarboxylic acid compound having the formula



wherein R_1 , R_2 , R_3 and R_4 can be either H, or $\text{NR}_5\text{R}_6\text{R}_7\text{R}_8$, where R_5 , R_6 , R_7 , and R_8 are each independently hydrogen or a linear or branched C_1 - C_6 hydrocarbon, or where two or more of R_5 , R_6 , R_7 , and R_8 together form a heterocyclic C_4 - C_7 ring, wherein R_9 and R_{10} may be independently defined in each repeat unit and each of which are independently hydrogen or a linear or branched C_1 - C_6 hydrocarbon, and wherein each of q , r , s , and t is a whole number from 0 to 4.

7. (Previously Presented) The composition of claim 1, wherein the two-carbon atom linkage alkanolamine compound has a boiling point of at least about 185°C and a flash point of at least about 95°C .

8. (Previously Presented) The composition of claim 1, wherein more than one two-carbon atom linkage alkanolamine compound is present in the composition.

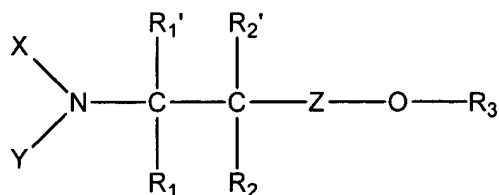
9. (Previously Presented) The composition of claim 1, wherein the corrosion inhibitor comprises gallic acid or catechol, and wherein the two-carbon atom linkage alkanolamine compound comprises 2-(2-aminoethoxy)-ethanol.

10 - 16. (Cancelled)

17. (Previously Presented) A resist and etching residue remover composition comprising:

from about 1 wt% to about 30 wt% of N,N-diethylhydroxylamine;

from about 20 wt% to about 80 wt% of a two-carbon atom linkage alkanolamine compound having the formula



wherein R_1 , R_1' , R_2 , R_2' , and R_3 are, independently in each case, hydrogen or a linear, branched, or cyclic hydrocarbon containing from 1 to 7 carbon atoms, wherein Z is a group having the formula $(-\text{Q}-\text{CR}_1\text{R}_1'-\text{CR}_2\text{R}_2'-)_m$, such that m is a whole number from 0 to 3, R_1 , R_1' , R_2 , and R_2' are independently defined in each repeat unit, if $m > 1$, within the parameters set forth for these moieties above, and Q is independently defined in each repeat unit, if $m > 1$, each Q being independently either -O- or $-\text{NR}_3-$, and wherein X and Y are, independently in each case, hydrogen, a C_1 - C_7 linear, branched, or cyclic hydrocarbon, or a group having the formula $-\text{CR}_1\text{R}_1'-\text{CR}_2\text{R}_2'-\text{Z}-\text{F}$, with F being either $-\text{O}-\text{R}_3$ or $-\text{NR}_3\text{R}_4$, where R_4 is defined similarly to R_1 , R_1' , R_2 , R_2' , and R_3 above, and with Z, R_1 , R_1' , R_2 , R_2' , and R_3 defined as above, or wherein X and Y are linked together form a nitrogen-containing heterocyclic C_4 - C_7 ring wherein the two-carbon atom linkage alkanolamine compound comprises 2-(2-aminoethylamino)-ethanol; and from about 5 wt% to about 45 wt% water,

wherein the composition is substantially free of polar organic solvents and of fluoride ions, and the composition is capable of removing residue from a metal or metal alloy substrate or a metal or metal alloy substrate layer, while maintaining an acceptably low etch rate with respect to the metal or metal alloy substrate or substrate layer.

18. (original) The substantially polar organic solvent-free composition of claim 17, wherein the composition is substantially free from corrosion inhibitors.

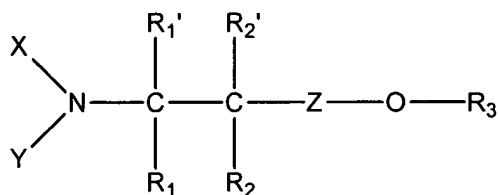
19. (original) The substantially polar organic solvent-free composition of claim 17, wherein the two-carbon atom linkage alkanolamine compound has a boiling point of at least about 185°C and a flash point of at least about 95°C.

20. (Currently Amended) The substantially polar organic solvent-free composition of claim 19, wherein the two-carbon atom linkage alkanolamine compound ~~comprises~~ is 2-(2-aminoethoxy)-ethanol.

21. (cancelled)

22. (original) The substantially polar organic solvent-free composition of claim 17, further comprising hydroxylamine, wherein the ratio of hydroxylamine derivative to hydroxylamine is from about 20:1 to about 1:20, by weight.

23. (Previously Presented) A resist and etching remover composition comprising:
from about 1 wt% to about 30 wt% of N,N-diethylhydroxylamine;
from about 20 wt% to about 80 wt% of a two-carbon atom linkage alkanolamine compound having the formula



wherein R₁, R₁', R₂, R₂', and R₃ are, independently in each case, hydrogen or a linear, branched, or cyclic hydrocarbon containing from 1 to 7 carbon atoms, wherein Z is a group having the formula $-(\text{-Q-CR}_1\text{R}_1'\text{-CR}_2\text{R}_2'\text{-})_m\text{-}$, such that m is a whole number from 0 to 3, R₁, R₁', R₂, and R₂' are independently defined in each repeat unit, if m>1, within the parameters set forth for these moieties above, and Q is independently defined in each repeat unit, if m>1, each Q being independently either -O- or -NR₃-, and wherein X and Y are, independently in each case,

hydrogen, a C₁-C₇ linear, branched, or cyclic hydrocarbon, or a group having the formula -CR₁R₁'-CR₂R₂'-Z-F, with F being either -O-R₃ or -NR₃R₄, where R₄ is defined similarly to R₁, R₁', R₂, R₂', and R₃ above, and with Z, R₁, R₁', R₂, R₂', and R₃ defined as above, or wherein X and Y are linked together form a nitrogen-containing heterocyclic C₄-C₇ ring, wherein the two-carbon atom linkage alkanolamine compound comprises 2-(2-aminoethylamino)-ethanol; and

from about 5 wt% to about 45 wt% water,

wherein the composition is substantially free of hydroxylamine and of fluoride ions, and the composition is capable of removing residue from a metal or metal alloy substrate or a metal or metal alloy substrate layer, while maintaining an acceptably low etch rate with respect to the metal or metal alloy substrate or substrate layer.

24. (original) The substantially hydroxylamine-free composition of claim 23, wherein the composition is substantially free from corrosion inhibitors.

25. (original) The substantially hydroxylamine-free composition of claim 23, wherein the two-carbon atom linkage alkanolamine compound has a boiling point of at least about 185°C and a flash point of at least about 95°C.

26. (Currently Amended) The substantially hydroxylamine-free composition of claim 25, wherein the two-carbon atom linkage alkanolamine compound ~~comprises~~ is 2-(2-aminoethoxy)-ethanol, or both.

27. (cancelled)

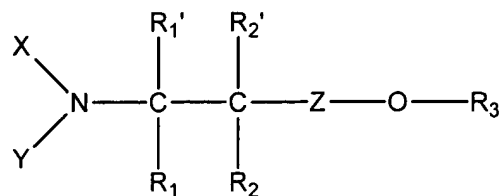
28. (original) The substantially hydroxylamine-free composition of claim 23, further comprising a polar organic solvent in an amount from about 5 wt% to about 15 wt%.

29. (original) The substantially hydroxylamine-free composition of claim 23, wherein the composition is substantially free from polar organic solvents.

30. (Previously Presented) A resist and etching residue remover composition comprising:

from about 5 wt% to about 30 wt% of N,N-diethylhydroxylamine; and

from about 20 wt% to about 80 wt% of a two-carbon atom linkage alkanolamine compound having the formula



wherein R_1 , R_1' , R_2 , R_2' , and R_3 are, independently in each case, hydrogen or a linear, branched, or cyclic hydrocarbon containing from 1 to 7 carbon atoms, wherein Z is a group having the formula $(-\text{Q}-\text{CR}_1\text{R}_1'-\text{CR}_2\text{R}_2'-)\text{m}-$, such that m is a whole number from 0 to 3, R_1 , R_1' , R_2 , and R_2' are independently defined in each repeat unit, if $m > 1$, within the parameters set forth for these moieties above, and Q is independently defined in each repeat unit, if $m > 1$, each Q being independently either -O- or -NR₃-, and wherein X and Y are, independently in each case, hydrogen, a C₁-C₇ linear, branched, or cyclic hydrocarbon, or a group having the formula -CR₁R₁'-CR₂R₂'-Z-F, with F being either -O-R₃ or -NR₃R₄, where R₄ is defined similarly to R_1 , R_1' , R_2 , R_2' , and R_3 above, and with Z, R_1 , R_1' , R_2 , R_2' , and R_3 defined as above, or wherein X and Y are linked together form a nitrogen-containing heterocyclic C₄-C₇ ring,

wherein the composition is substantially free of water and of fluoride ions, and the composition is capable of removing residue from a metal or metal alloy substrate or a metal or metal alloy substrate layer, while maintaining an acceptably low etch rate with respect to the metal or metal alloy substrate or substrate layer.

31 – 41 (Cancelled)